Refine Search

Search Results -

Terms	Documents
(specific adj impedance) and frequency and plasma	19

Database:
US Pre-Grant Publication Full-Text Database
US Patents Full-Text Database
US OCR Full-Text Database
EPO Abstracts Database
JPO Abstracts Database
Derwent World Patents Index
IBM Technical Disclosure Bulletins

Search:
L7

[Refine Search]

[Recall Text]   [Clear]   [Interrupt]

Search History

DATE: Sunday, December 19, 2004   Printable Copy   Create Case

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=OR

Set Name side by side	Query	Hit Count	Set Name result set
L7	(specific adj impedance) and frequency and plasma	19	L7
L6	(specific adj impedance) and frequency and termination and plasma	0	L6
L5	(reactive adj termination) and plasma	12	L5
L4	(reactive adj termination) and (secondary adj frequencies) and plasma	0	L4
L3	L2 and voltage and current	8	L3
L2	L1 and (regulat$3 or limit$3) and components	9	L2
L1	(termination adj impedance) and RF and plasma and process$3 and frequenc$3	12	L1

END OF SEARCH HISTORY

Refine Search

Search Results -

Terms	Documents
L10 and harmonics	2

Database:
US Pre-Grant Publication Full-Text Database
US Patents Full-Text Database
US OCR Full-Text Database
EPO Abstracts Database
JPO Abstracts Database
Derwent World Patents Index
IBM Technical Disclosure Bulletins

Search:
L13

[Refine Search]

[Recall Text ⬍]   [Clear]   [Interrupt]

Search History

DATE: Sunday, December 19, 2004   Printable Copy   Create Case

Set Name side by side	Query	Hit Count	Set Name result set
DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=OR			
L13	L10 and harmonics	2	L13
L12	L7 and (secondary adj frequencies)	0	L12
L11	L10 and (secondary adj frequencies)	0	L11
L10	L9 and impedance	4	L10
L9	L8 and inductor	4	L9
L8	L7 and (variable adj capacitor)	6	L8
L7	L6 and resonan$2 and frequencies	41	L7
L6	L1 and 315/$.ccls.	61	L6
L5	L3 and 315/$.ccls.	0	L5
L4	L3 and plasma	7	L4
L3	RF and (fundamental near2 frequency) and match$3 and (secondary adj frequencies)	13	L3
L2	L1 and (secondary adj frequencies)	2	L2

L1   (plasma adj chamber) and deposit$3 and films and substrate and limit$3   1257   L1
      and voltage and current

END OF SEARCH HISTORY